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Park**

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(54) **LIGHT-EMITTING DEVICE AND
FABRICATION METHOD THEREOF**

(75) Inventor: **KyungWook Park**, Seoul (KR)

(73) Assignee: **LG Innotek Co., Ltd.**, Seoul (KR)

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(2013.01); **H01L 33/405** (2013.01); **H01L**
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(2013.01)

(58) **Field of Classification Search**

None

See application file for complete search history.

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Primary Examiner — Johannes P Mondt

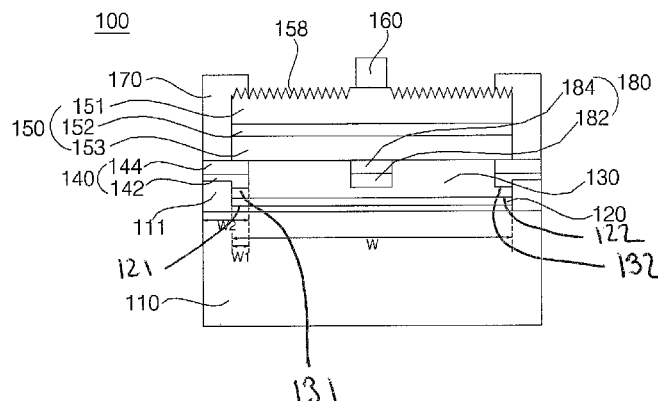
(74) *Attorney, Agent, or Firm* — KED & Associates LLP

(57)

ABSTRACT

Disclosed is a light-emitting device including a conductive support substrate, a reflective layer arranged on the conductive support substrate, a first electrode layer arranged on the reflective layer and provided with a step in at least one region of the edge thereof, a protective layer arranged on the step, and a light-emitting structure arranged on the first electrode layer and the protective layer, the light-emitting structure including a first conductive semiconductor layer, a second conductive semiconductor layer and an active layer interposed between the first conductive semiconductor layer and the second conductive semiconductor layer, wherein at least one region of the reflective layer and the first electrode layer vertically overlaps the protective layer. Based on this configuration, the light-emitting device can exhibit improved adhesion between the electrode layer and the reflective layer and be provided with a wider reflective layer, thus improving brightness.

16 Claims, 11 Drawing Sheets



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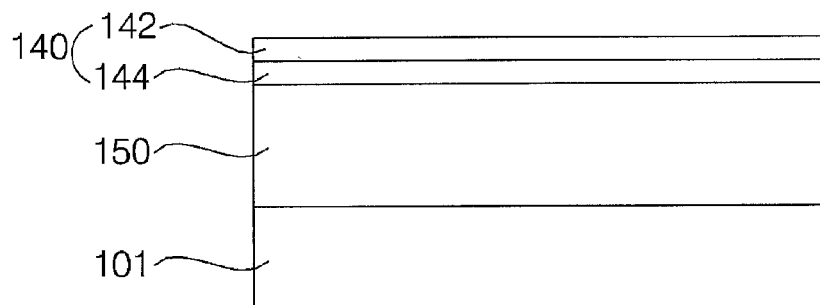


FIG. 3

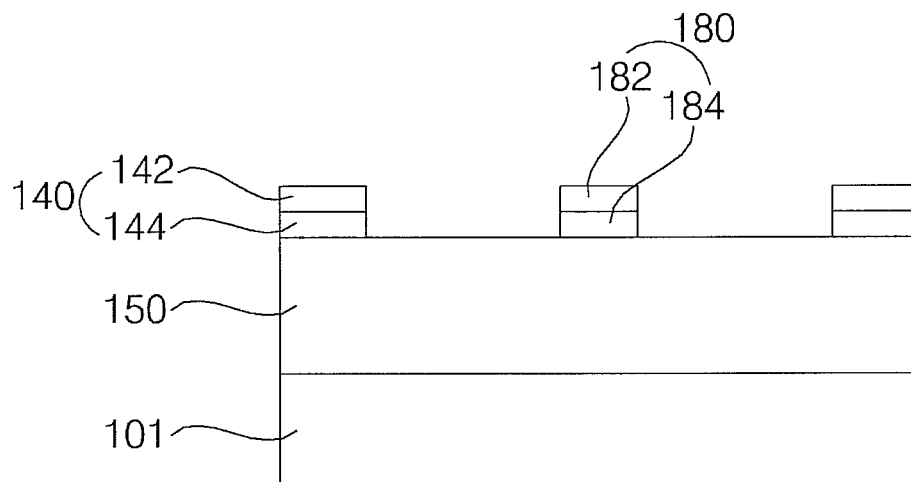


FIG. 4

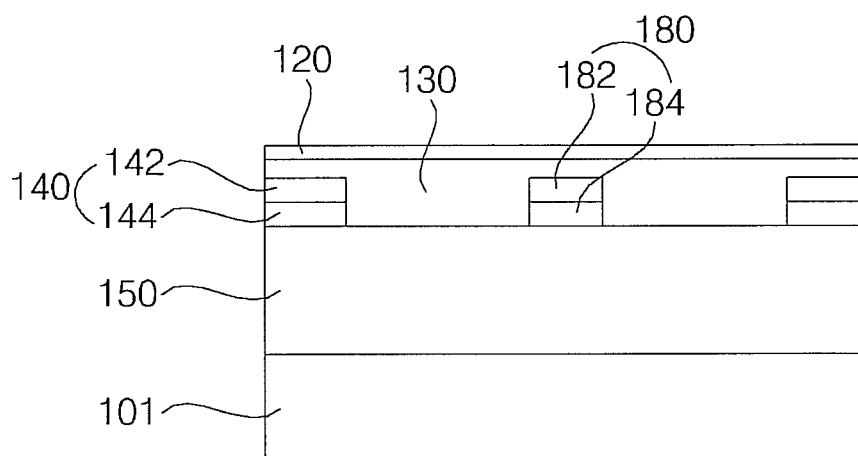


FIG. 5

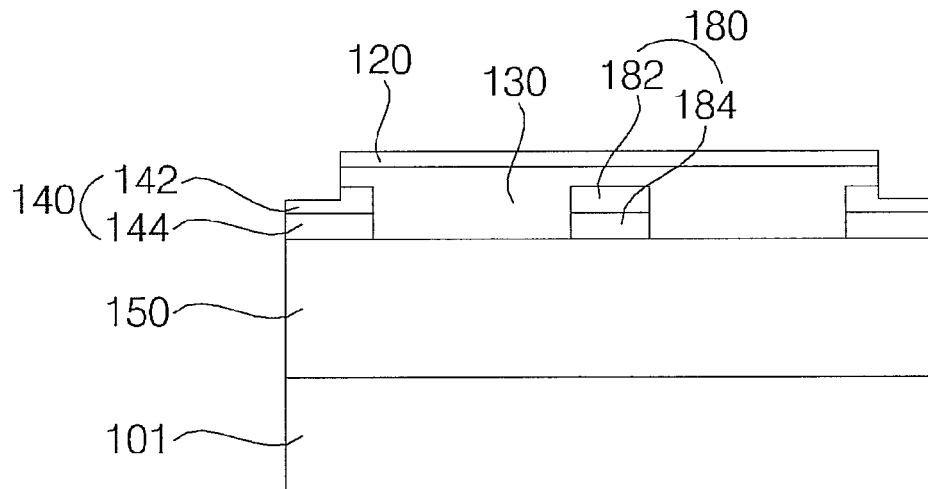


FIG. 6

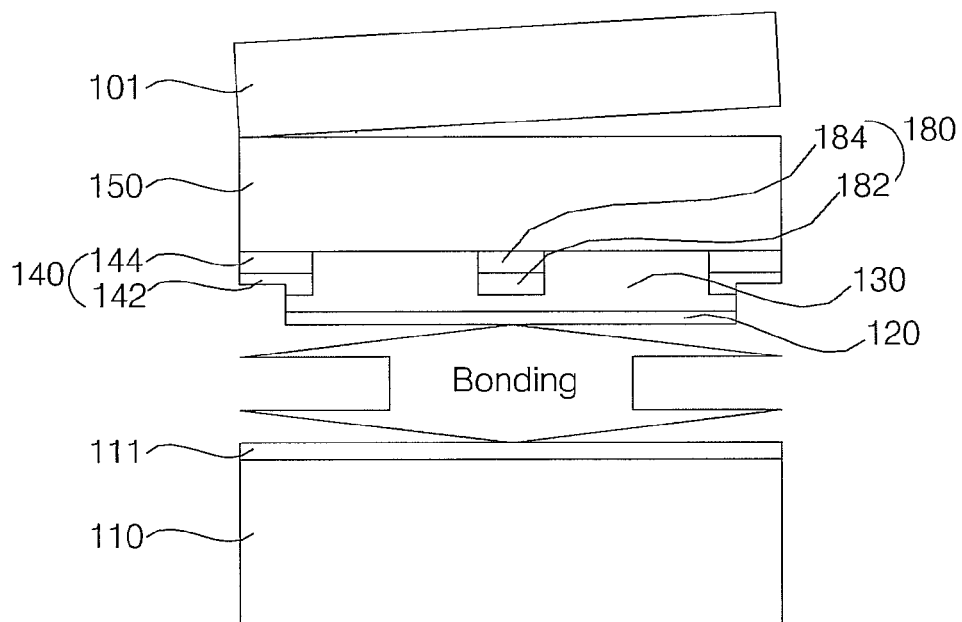


FIG. 7

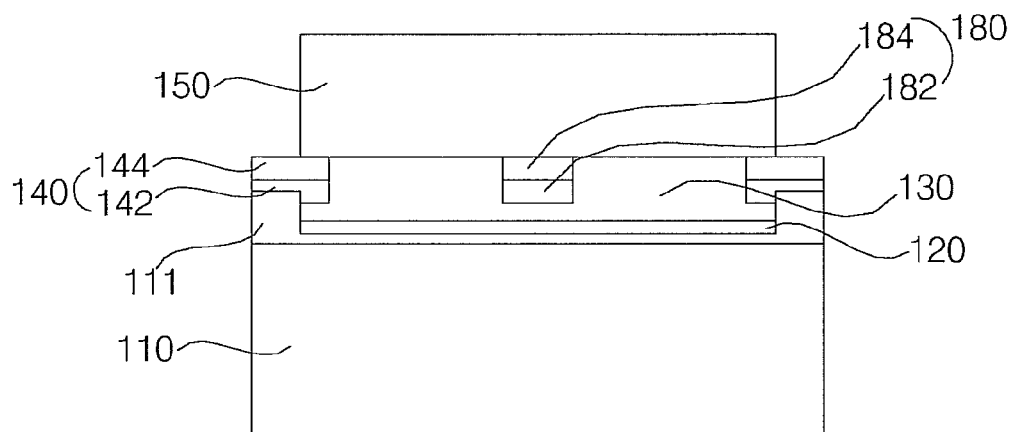


FIG. 8

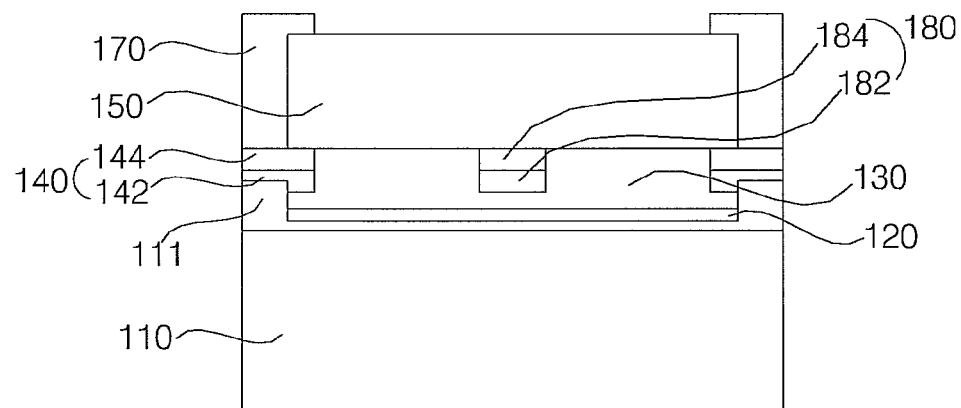


FIG. 9

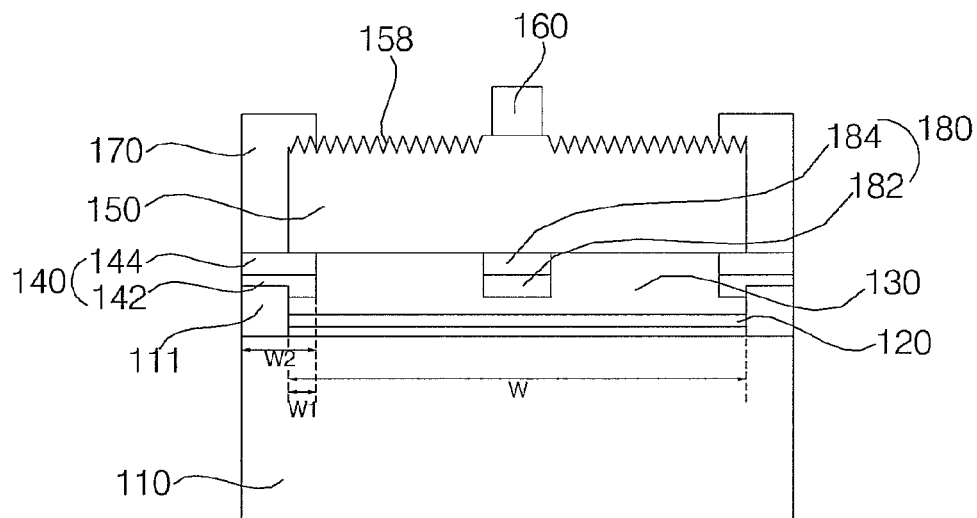


FIG. 10A

200

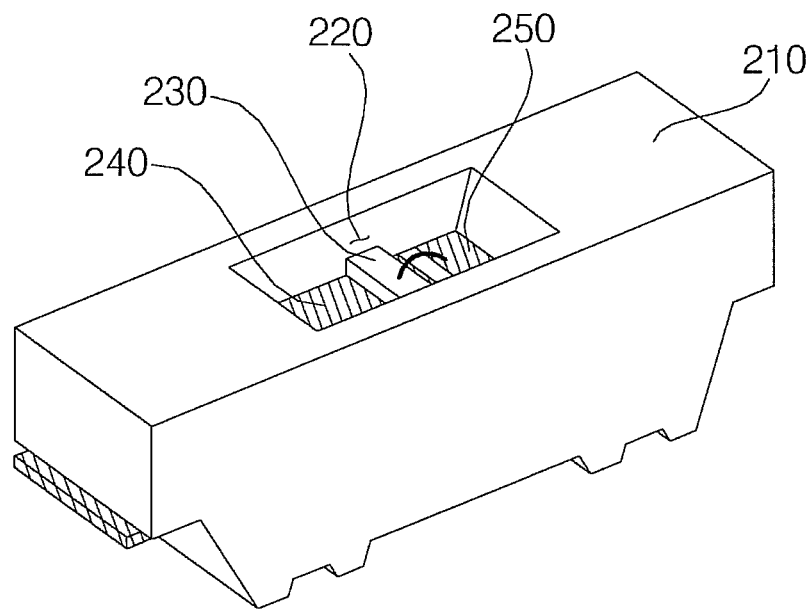


FIG. 10B

200

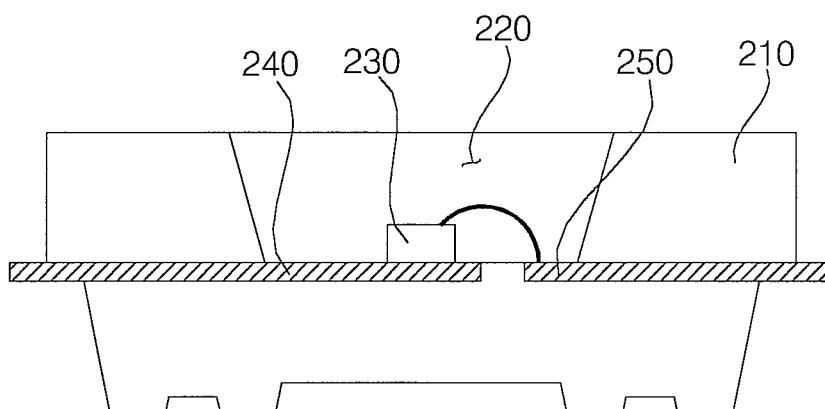


FIG. 11A

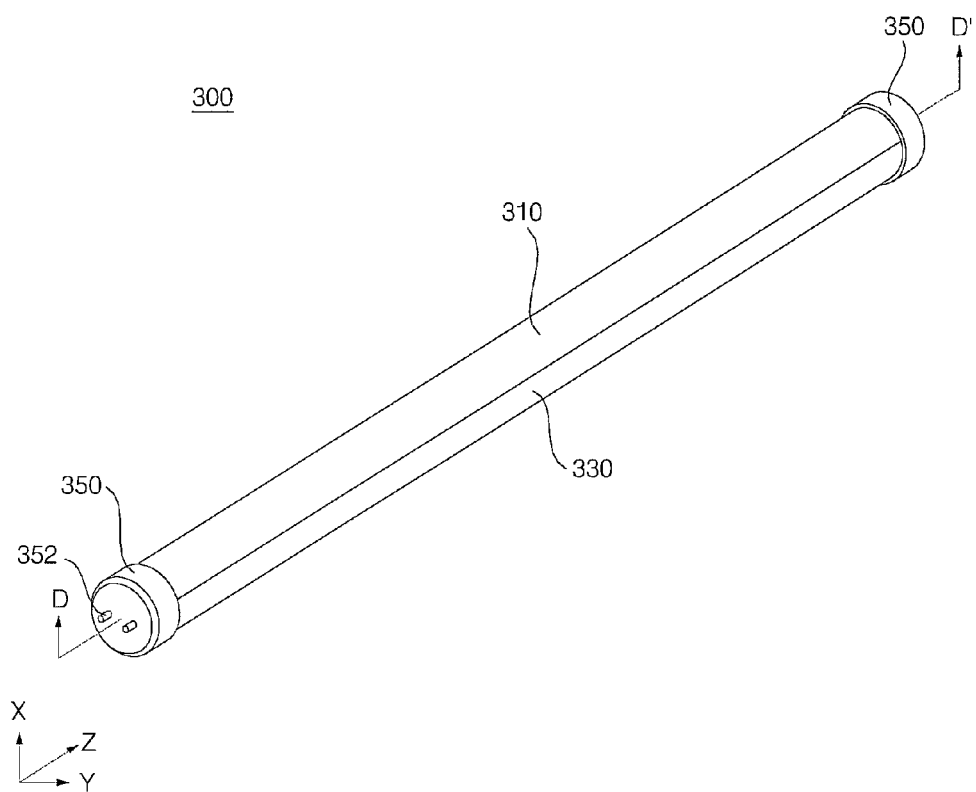


FIG. 11B

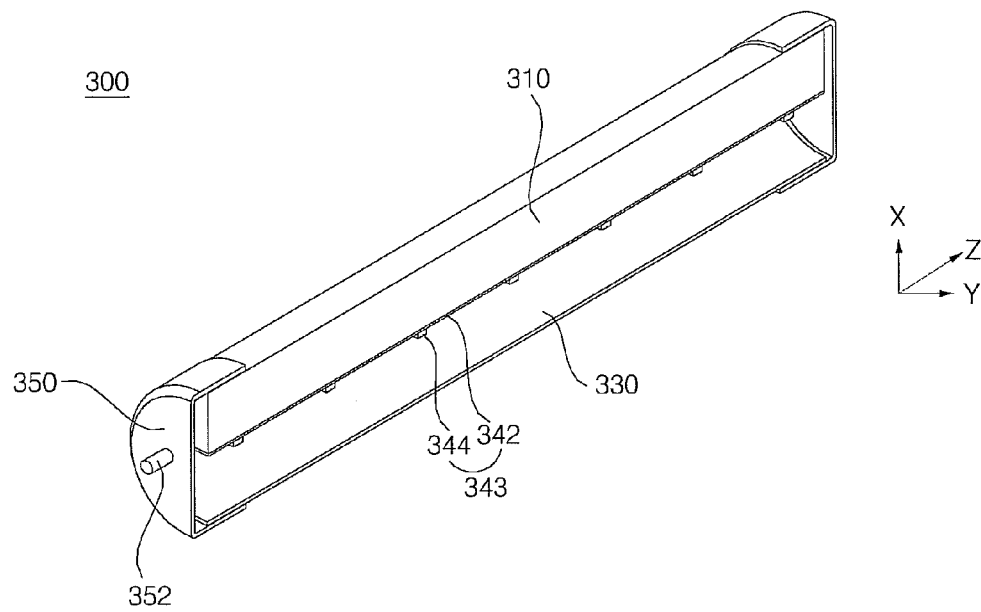


FIG. 12

400

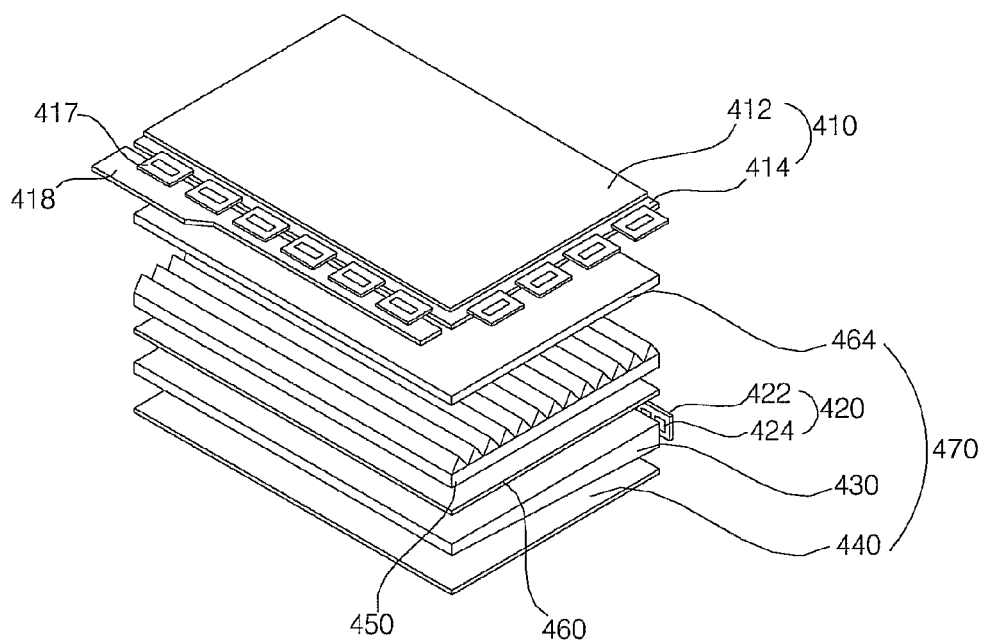
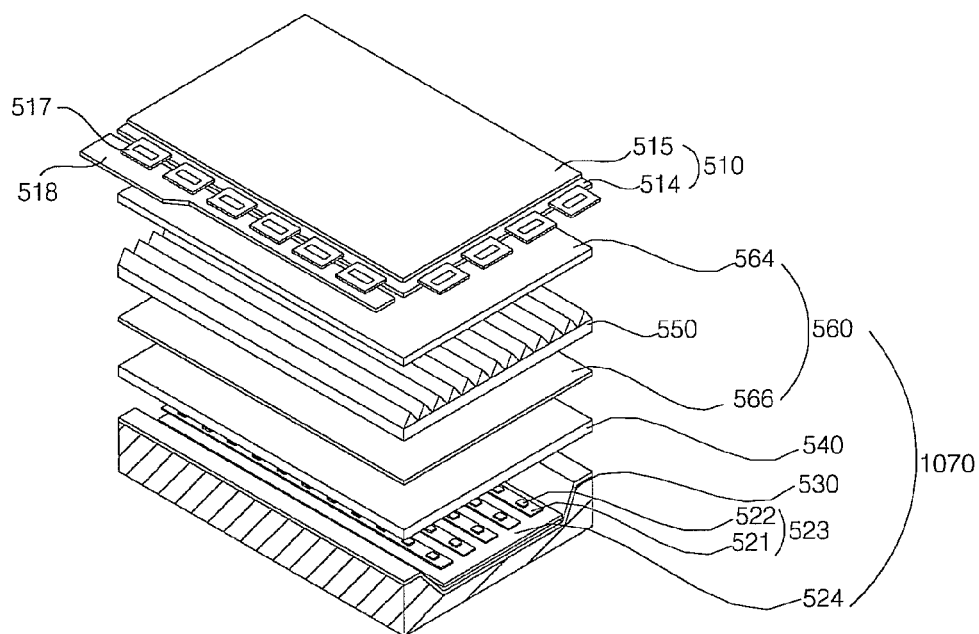


FIG. 13

500



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LIGHT-EMITTING DEVICE AND FABRICATION METHOD THEREOF

CROSS-REFERENCE TO RELATED APPLICATION

This application claims the priority benefit of Korean Patent Application No. 10-2010-0064487, filed on Jul. 5, 2010 in the Korean Intellectual Property Office, the disclosure of which is incorporated herein by reference.

BACKGROUND

1. Field

Embodiments relate to a light-emitting device and a fabrication method thereof.

2. Description of the Related Art

A light-emitting diode (LED) is a device which converts electric signals into light using characteristics of compound semiconductors. LEDs are now being applied to devices such as home appliances, remote controls, electronic signboards, displays, a variety of automatic appliances and the like and the application range thereof continues to expand.

Generally, a miniaturized LED is fabricated as a surface mount device such that it can be directly mounted to a printed circuit board (PCB). Accordingly, an LED lamp used as a display device is also developed in a surface mount device-type. Such a surface mount device may replace a conventional lamp and is used as lighting displays, character displays, image displays and the like, rendering various colors.

As the application range of LEDs widens, brightness required for lights in daily use and lights for structural signals increases. Accordingly, it is important to increase brightness of LEDs.

SUMMARY

Therefore, the embodiments provide a light-emitting device and a fabrication method thereof, to improve adhesion force between an electrode layer and a reflective layer, and enhance brightness through fabrication of a wider reflective layer.

In accordance with one aspect of the embodiment, provided is a light-emitting device including: a conductive support substrate; a reflective layer arranged on the conductive support substrate; a first electrode layer arranged on the reflective layer and provided with a step in at least one region of the edge thereof; a protective layer arranged on the step; and a light-emitting structure arranged on the first electrode layer and the protective layer, the light-emitting structure including a first conductive semiconductor layer, a second conductive semiconductor layer and an active layer interposed between the first conductive semiconductor layer and the second conductive semiconductor layer, wherein at least one region of the reflective layer and the first electrode layer vertically overlaps the protective layer.

The reflective layer and the first electrode layer may have an identical width.

A width of the region where the reflective layer and the first electrode layer vertically overlap the protective layer may be 15 to 30 μm .

A width of the region where the reflective layer and the first electrode layer overlap the protective layer may be 0.11- to 0.23-fold of the width of the protective layer.

The light-emitting device may further include a light extraction structure arranged on the light-emitting structure.

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The light extraction structure may include a roughness having a predetermined roughness level.

The light-emitting device may further include an intermediate layer interposed between the first conductive semiconductor layer and the second conductive semiconductor layer, wherein the intermediate layer is an electron blocking layer.

The light-emitting device may further include a second electrode layer arranged on the light-emitting structure.

The light-emitting device may further include a current blocking layer arranged under the light-emitting structure such that the current blocking layer vertically overlaps the second electrode layer in at least one region.

The first electrode layer may include a step arranged in a region where the first electrode layer vertically overlaps the second electrode layer, wherein the current blocking layer is arranged in the step.

The light-emitting device may further include an insulating layer arranged at the side of the light-emitting structure.

The protective layer may include at least a first layer and a second layer arranged under the first layer.

The first layer contains silicon dioxide (SiO_2) and the second layer may contain aluminum oxide (Al_2O_3).

The reflective layer may contain at least one of Ag, Ni, Al, Rh, Pd, Ir, Ru, Mg, Zn, Pt, Au, Hf, IZO, IZTO, IAZO, IGZO, IGTO, AZO and ATO.

The area of the reflective layer may larger than the area of the active layer.

In accordance with another aspect, provided is a lighting system including the light-emitting device of the embodiments.

In accordance with another aspect, provided is a method for fabricating a light-emitting device including: forming a light-emitting structure on a growth substrate, the light-emitting structure including at least a first conductive semiconductor layer, an active layer and a second conductive semiconductor layer; forming a protective layer in at least one region of the edge of the light-emitting structure; and simultaneously baking the first electrode layer and the reflective layer arranged on the protective layer and the light-emitting structure.

The method may further include; simultaneously etching the edges of the first electrode layer and the reflective layer; forming a conductive support substrate on the reflective layer; removing the growth substrate; and etching at least one region of the edge of the light-emitting structure such that at least one region of the protective layer is etched.

The method may further include; forming roughness on the first conductive semiconductor layer; and forming a second electrode layer on the first conductive semiconductor layer.

The forming the protective layer may include: forming a first layer containing silicon dioxide (SiO_2); and forming a second layer containing aluminum oxide (Al_2O_3) on the first layer.

BRIEF DESCRIPTION OF THE DRAWINGS

The above and other features and other advantages of the embodiment will be more clearly understood from the following detailed description taken in conjunction with the accompanying drawings, in which:

FIG. 1 is a sectional view illustrating the structure of a light-emitting device according to one embodiment;

FIGS. 2 to 9 are sectional views illustrating a method for fabricating the light-emitting device of FIG. 1;

FIG. 10A is a perspective view illustrating a lighting device including a light-emitting device package according to one embodiment;

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FIG. 10B is a sectional view of the light-emitting device package illustrated in FIG. 10A;

FIG. 11A is a perspective view illustrating a lighting device including a light-emitting device according to one embodiment;

FIG. 11B is a sectional view of the lighting device taken along the line A-A of FIG. 1;

FIG. 12 is an exploded perspective view illustrating a liquid crystal display including the light-emitting device according to another embodiment; and

FIG. 13 is an exploded perspective view illustrating a liquid crystal display including the light-emitting device according to one embodiment.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

Reference will now be made in detail to the embodiments, examples of which are illustrated in the accompanying drawings.

Advantages and characteristics of the embodiments and methods for addressing the same will be clearly understood from the following embodiments taken in conjunction with the annexed drawings. However, the embodiments are not limited to the embodiments and realized by various forms thereof. The embodiments are only provided to more completely illustrate the embodiments and the scope of the embodiments are defined by only claims. Accordingly, in some embodiments, well-known processes, well-known device structures and well-known techniques are not illustrated in detail to avoid unclear interpretation of the embodiments. The same reference numbers will be used throughout the specification to refer to the same or like parts.

Prior to description of the embodiments, it will be understood that, when an element is referred to as being formed “on or under” another element, the two elements may directly contact each other or may be indirectly arranged such that at least one intervening element is interposed therebetween. Further, the term “on or under” of an element may mean “on” as well as “under” the element.

Terms used in the specification are only provided to illustrate the embodiments and should not be construed as limiting the scope and spirit of the embodiments. In the specification, a singular form of terms includes plural forms thereof, unless specifically mentioned otherwise. In the term “comprises” and/or “comprising” as herein used, the mentioned component, step, operation and/or device is not excluded from presence or addition of one or more other component, steps, operations and/or devices.

Unless defined otherwise, all terms (including technical and scientific terms) used herein may be intended to have meanings understood by those skilled in the art. In addition, terms defined in general dictionaries should not be interpreted abnormally or exaggeratedly, unless clearly specifically defined.

In the drawings, the thicknesses or sizes of respective layers are exaggerated, omitted or schematically illustrated for clarity and convenience of description. Therefore, the sizes of respective elements do not wholly reflect actual sizes thereof.

Although terms such as first and second are used to illustrate a variety of elements, components, layers and/or regions, the terms should not be construed as limiting the elements, components, layers and/or regions.

In addition, angles and directions referred to during description of a structure of a light emitting device are described based on illustration in the drawings. In the description of the structure of the light emitting device, if reference

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points with respect to the angles and positional relations are not clearly stated, the related drawing will be referred to.

Reference will now be made in detail to the embodiments, examples of which are illustrated in the accompanying drawings.

FIG. 1 is a sectional view illustrating the structure of a light-emitting device according to one embodiment.

Referring to FIG. 1, the light-emitting device 100 according to this embodiment includes: a conductive support substrate 110; a reflective layer 120 arranged on the conductive support substrate 110; a first electrode layer 130 arranged on the reflective layer 120 and provided with a step in at least one region of the edge thereof; a protective layer 140 arranged on the step; and a light-emitting structure 150 arranged on the first electrode layer 130 and the protective layer 140, the light-emitting structure 150 including a first conductive semiconductor layer 151, a second conductive semiconductor layer 153 and an active layer 152 interposed between the first conductive semiconductor layer 151 and the second conductive semiconductor layer 153, wherein at least one region of the reflective layer 120 and the first electrode layer 130 vertically overlaps the protective layer 140 in at least one region. FIG. 1 shows at least one region 121 (or at least one first region) of the reflective layer 120, and at least one region 122 (or at least one first region) of the reflective layer 120.

The conductive support substrate 110 may be made of a thermally conductive material or a conductive material such as a metal or conductive ceramic. The conductive support substrate 110 may be a mono-layer, or a di- or multi-layer.

That is, the conductive support substrate 110 may be made of a metal selected from Au, Ni, W, Mo, Cu, Al, Ta, Ag, Pt and Cr, or an alloy thereof and may be a laminate including two or more different materials.

Such a conductive support substrate 110 facilitates emission of heat generated by the light-emitting device 100 and improves thermal stability of the light-emitting device 100.

In a case where a part of light generated in the active layer 152 of the light-emitting structure 150 is directed toward the conductive support substrate 110, the reflective layer 120 reflects the light toward the top of the light-emitting device 100, thus improving light extraction efficiency of the light-emitting device 100. Accordingly, the reflective layer 120 may be made of a material having a high light reflectance. For example, the reflective layer 120 is made of a metal selected from Ag, Ni, Al, Rh, Pd, Ir, Ru, Mg, Zn, Pt, Au, Hf and combinations thereof, or is a multi-layer composed of the metal and a light-transmitting conductive material such as IZO, IZTO, IAZO, IGZO, IGTO, AZO and ATO. In addition, the reflective layer 120 may be a laminate of IZO/Ni, AZO/Ag, IZO/Ag/Ni, AZO/Ag/Ni or the like.

The first electrode layer 130 may be have a multi-layer structure and for example, may include, without being limited to, an ohmic layer (not shown) and a bonding layer (not shown).

The ohmic layer (not shown) ohmic contacts the bottom of the light-emitting structure 150 and may include a plurality of layers or patterns. The ohmic layer (not shown) may be selected from light-transmitting electrode layers and metals. The ohmic layer may be realized as a mono- or multi-layer using one or more selected from indium tin oxide (ITO), indium zinc oxide (IZO), indium zinc tin oxide (IZTO), indium aluminum zinc oxide (IAZO), indium gallium zinc oxide (IGZO), indium gallium tin oxide (IGTO), aluminum zinc oxide (AZO), antimony tin oxide (ATO), gallium zinc oxide (GZO), IrOx, RuOx, RuOx/ITO, Ni, Ag, Ni/IrOx/Au, and Ni/IrOx/Au/ITO. The ohmic layer (not shown) facilitates

incorporation of carriers in the second semiconductor layer **153** and may be not formed in some cases.

In addition, the first electrode layer **130** may include a bonding layer (not shown) and the bonding layer (not shown) may contain, as a barrier metal or a bonding metal, at least one selected from Ti, Au, Sn, Ni, Cr, Ga, In, Bi, Cu, Ag and Ta, without being limited thereto.

Meanwhile, the reflective layer **120** and the first electrode layer **130** may have the same width (W) and may have superior adhesion force, since the reflective layer **120** and the first electrode layer **130** are formed through a simultaneous baking process.

The first electrode layer **130** may include a step **131** (also referred to as a first step) in least one region of the edge thereof and the protective layer **140** may be arranged on the step. When the reflective layer **120** and the first electrode layer **130** formed by simultaneous baking are etched, the protective layer **140** prevents the light-emitting structure **150** from being etched. At this time, the etching method may be, for example, dry etching. FIG. 1 also shows a step **132** (also referred to as a second step).

In addition, the protective layer **140** may have a multi-layer structure and may, for example, include a first layer **144** and a second layer **142** arranged thereon. The first layer **144** may contain silicon dioxide (SiO₂) and the second layer **142** may contain aluminum oxide (Al₂O₃), thus more efficiently protecting the light-emitting structure **150** against etching.

The protective layer **140** may be arranged such that it vertically partially overlaps the first electrode layer **130** and the reflective layer **120**.

As mentioned below, after the first electrode layer **130** and the reflective layer **120** undergo simultaneous baking and single etching, the reflective layer **120** is arranged such that it vertically partially overlaps the protective layer **140** and has a wider area. This maximizes reflectivity of the reflective layer **120** and improves the luminous efficiency of the light-emitting diode **100**. In addition, when the first electrode layer **130** and the reflective layer **120** undergo simultaneous baking and single etching processes, the reflective layer **120** and the first electrode layer **130** may have the same width (W).

Meanwhile, the width W₁ of the region in which the reflective layer **120** and the first electrode layer **130** vertically partially overlap the protective layer **140** may be 15 to 30 μm. Taking into consideration the fact that the protective layer **140** has a width W₂ of about 130 μm, the width W₁ of the region in which the reflective layer **120** and the first electrode layer **130** vertically partially overlap the protective layer may be 0.11- to 0.23-fold of the width W₂ of the protective layer **140**.

The light-emitting structure **150** contacts the first electrode layer **130** and the protective layer **140** and may include at least the first conductive semiconductor layer **151**, the active layer **152** and the second conductive semiconductor layer **153**, and the active layer **152** may be interposed between the first conductive semiconductor layer **151** and the second conductive semiconductor layer **153**. In addition, the light-emitting structure **150** may further include a light extraction structure **158** and a second electrode layer **160** arranged on the light-emitting structure **150**.

The first semiconductor layer **151** may be realized by an n-type semiconductor layer and may supply electrons to the active layer **152**. The first semiconductor layer **151** may be selected from semiconductor materials having a formula of In_xAl_yGa_{1-x-y}N (0 ≤ x ≤ 1, 0 ≤ y ≤ 1, 0 ≤ x + y ≤ 1), such as GaN, AlN, AlGaIn, InGaIn, InAlGaIn and AlInN and may be doped with an n-type dopant such as Si, Ge and Sn.

The active layer **152** may be arranged under the first conductive semiconductor layer **151**.

The active layer **152** may have a single or multi-quantum well structure, a quantum wire structure, a quantum dot structure or the like made of a compound semiconductor material composed of Group III-V elements.

In the case where the active layer **152** has a quantum well structure, for example, it may have a single or multi-quantum well structure including a well layer having the formula of In_xAl_yGa_{1-x-y}N (0 ≤ x ≤ 1, 0 ≤ y ≤ 1, 0 ≤ x + y ≤ 1) and a barrier layer having the formula of In_aAl_bGa_{1-a-b}N (0 ≤ x ≤ 1, 0 ≤ y ≤ 1, 0 ≤ x + y ≤ 1). The well layer may be made of a material having a band gap smaller than that of the barrier layer.

The second conductive semiconductor layer **153** may be realized by a p-type semiconductor layer to supply holes to the active layer **152**. The second conductive semiconductor layer **153** may for example be made of a semiconductor material having a formula of In_xAl_yGa_{1-x-y}N (0 ≤ x ≤ 1, 0 ≤ y ≤ 1, 0 ≤ x + y ≤ 1) such as GaN, AlN, AlGaIn, InGaIn, InN, InAlGaIn and AlInN and may be doped with a p-type dopant such as Mg, Zn, Ca, Sr and Ba.

Meanwhile, the first conductive semiconductor layer **151**, the active layer **152** and the second conductive semiconductor layer **153** may be formed by a method which includes, but is not limited to, metal organic chemical vapor deposition (MOCVD), chemical vapor deposition (CVD), plasma-enhanced chemical vapor deposition (PECVD), molecular beam epitaxy (MBE), hydride vapor phase epitaxy (HVPE) and sputtering.

Meanwhile, an intermediate layer (not shown) may be arranged between the first conductive semiconductor layer **151** and the second conductive semiconductor layer **153**, the intermediate layer (not shown) may be an electron blocking layer which prevents a phenomenon in which electrons supplied from the first conductive semiconductor layer **151** to the active layer **152** are not recombined in the active layer **152** and instead are supplied to the second conductive semiconductor layer **153**, when high current is applied thereto. The intermediate layer (not shown) has a larger band gap than the active layer **152**, thus preventing the phenomenon in which electrons supplied from the first conductive semiconductor layer **151** to the active layer **152** are not recombined in the active layer **152** and instead are supplied to the second conductive semiconductor layer **153**. Accordingly, this increases the possibility of recombination between electrons and holes in the active layer **152** and prevents current leakage.

Meanwhile, the intermediate layer (not shown) may have a band gap larger than the barrier layer included in the active layer **152** and may for example be made of a p-type Al-containing semiconductor layer such as AlGaIn, without being limited thereto.

Meanwhile, the light-emitting structure **150** may include a third semiconductor layer (not shown) having polarity opposite to the first conductive semiconductor layer **151**, arranged on the first conductive semiconductor layer **151**. In addition, the first conductive semiconductor layer **151** may be realized by a p-type semiconductor layer and the second conductive semiconductor layer **153** may be realized by an n-type semiconductor layer. As a result, the light-emitting device **150** may have at least one of n-p, p-n, n-p-n and p-n-p junction structures.

Meanwhile, the second electrode layer **160** may be arranged on the first conductive semiconductor layer **151** such that it is electrically connected to the first conductive semiconductor layer **151**, and the second electrode layer **160** may include an electrode having at least one pad and/or predetermined pattern. The second electrode layer **160** may be arranged in a center, peripheral or edge region on the first conductive semiconductor layer **151** and the region is not

limited thereto. Meanwhile, the second electrode layer **160** may be arranged in a region other than regions provided on the first conductive semiconductor layer **151** and the position thereof is not limited thereto.

The second electrode layer **160** may be a mono- or multi-layer made of a conductive material such as a metal selected from In, Co, Si, Ge, Au, Pd, Pt, Ru, Re, Mg, Zn, Hf, Ta, Rh, Ir, W, Ti, Ag, Cr, Mo, Nb, Al, Ni, Cu, and WTi, or an alloy thereof.

The light-emitting structure **150** may further be provided at the top thereof with a light extraction structure **158**. The light extraction structure **158** may be arranged in partial regions or over the entirety of the first conductive semiconductor layer **151**. The light extraction structure **158** may be formed by etching at least one region of the upper surface of the first conductive semiconductor layer **151** and the formation method is not limited thereto. The etching process includes a wet or/and dry etching process. After the etching process, the upper surface of a light-transmitting electrode layer (not shown) or the upper surface of the first conductive semiconductor layer **151** may have roughness which constitutes the light extraction structure **158**. The roughness having a random size may be irregularly formed, but is not limited thereto. The roughness includes at least one of a texture pattern, a concave-convex pattern and an uneven pattern.

The cross-section of the roughness may have various shapes, such as a cylinder, a polyprism, a cone, a polypyr- amid, a circular truncated cone and a frustum of a pyramid, and preferably has a conical or polypyr- amidal shape.

Meanwhile, the light extraction structure **158** may be formed by a photo-electro chemical (PEC) method, but formation of the light extraction structure **158** is not limited thereto. When the light extraction structure **158** is formed on the upper surface of the light-transmitting electrode layer **151**, re-absorption of light generated from the active layer **152** into the active layer **152** or scattering of the light due to total reflection of the light by the upper surface of the light-trans- mitting electrode layer (not shown) or the first semiconductor layer **151** is prevented, thereby contributing to improvement of light extraction efficiency of the light-emitting device **100**.

A current blocking layer **180** may be arranged under the light-emitting structure **150** such that the current blocking layer **180** vertically overlaps the second electrode layer **160** in at least one region. In addition, the first electrode layer **130** may be provided with a step in which the current blocking layer **180** is arranged.

In a case where the first semiconductor layer **151** is realized by an n-type semiconductor layer, the current blocking layer **180** prevents current crowding in which electrons supplied through the second electrode layer **160** are concentrated at only the bottom of the second electrode layer **160**.

The current blocking layer **180** may be formed simulta- neously with the protective layer **140** as mentioned below and may be composed of a first layer **184** containing silicon diox- ide (SiO_2) or a second layer **182** containing aluminum oxide (Al_2O_3), similar to the protective layer **140**.

The light-emitting device **100** may include an insulating layer **170** arranged at the side of the light-emitting structure **150**. The insulating layer **170** may be made of an insulating material such as silicon oxide (SiO_2) or silicon nitride (Si_3N_4) and may extend from the top of the protective layer **140**, which does not vertically overlap the light-emitting structure **150** along the side of the light-emitting structure **150** to the partial top of the first semiconductor layer **151**.

FIGS. 2 to 9 are sectional views illustrating a method for fabricating the light-emitting device.

Referring to FIG. 2, a light-emitting structure **150** is formed on a growth substrate **101**.

The growth substrate **101** is selected from the group con- sisting of sapphire (Al_2O_3), GaN, SiC, ZnO, Si, GaP, InP and GaAs. Although not illustrated in the drawings, a buffer layer (not shown) may be formed between the growth substrate **101** and the light-emitting structure **150**.

The buffer layer (not shown) may be made of a compound of Group III and V elements, but may be selected from GaN, InN, AlN, InGaN, AlGaIn, InAlGaIn and AlInN and may be doped with a dopant.

An undoped semiconductor (not shown) may be arranged on the growth substrate **101** or the buffer layer (not shown), at least one of the buffer layer (not shown) and undoped semi- conductor layer (not shown) may be formed or be not formed, and this structure is not limited.

The light-emitting structure **150** may include at least the first conductive semiconductor layer, the active layer and the second conductive semiconductor layer, and this structure is defined above and a detailed explanation thereof is thus omit- ted.

The first layer **144** and the second layer **142** to form the protective layer **140** and the current blocking layer **180**, respectively, may be sequentially formed in separate regions on the light-emitting structure **150** by a method such as sput- tering.

The first layer **144** may contain silicon dioxide (SiO_2) and the second layer **142** may contain aluminum oxide (Al_2O_3).

As shown in FIG. 3, the first layer **144** and the second layer **142** are patterned using (not shown) a mask provided with an opening in regions where the protective layer **140** and the current blocking layer **180** are to be formed, and then baked at 600°C . or more to form the protective layer **140** and the current blocking layer **180**.

In FIG. 4, the first electrode layer **130** and the reflective layer **120** are simultaneously formed. That is, the formation of the first electrode layer **130** and the reflective layer **120** may be carried out by sequentially forming these layers by a method such as sputtering, followed by simultaneously bak- ing. When the first electrode layer **130** and the reflective layer **120** are formed by simultaneous baking as mentioned above, adhesion between the first electrode layer **130** and the reflective layer **120** may be improved.

Referring to FIG. 5, peripheral regions of the first electrode layer **130** and the reflective layer **120** are mesa-etched. The mesa etching may be carried out by dry etching. At this time, since the first electrode layer **130** and the reflective layer **120** are simultaneously etched, the first electrode layer **130** and the reflective layer **120** may have the same width (W).

Accordingly, the reflective layer **120** may have a wider area, thus exhibiting maximum reflection properties and improving luminous efficiency of the light-emitting diode **100**.

In addition, after the first electrode layer **130** and the reflec- tive layer **120** are mesa-etched, the reflective layer **120** verti- cally partially overlaps the protective layer **140** and the width W_1 of the region where the reflective layer **120** vertically partially overlaps the protective layer **140** may be 15 to $30\mu\text{m}$. At this time, taking into consideration the fact that the width W_2 of the protective layer **140** is about $130\mu\text{m}$, the width W_1 of region where the reflective layer **120** vertically partially overlaps the protective layer **140** may be 0.11- to 0.23-fold of the width W_2 of the protective layer **140**.

The protective layer **140** prevents the light-emitting struc- ture **150** from being etched, when the reflective layer **120** and the first electrode layer **130** are dry-etched.

Referring to FIG. 6, a conductive support member or a conductive support substrate **110** may be arranged on the reflective layer **120**. The conductive support substrate **110** may be adhered to the reflective layer **120** by an adhesion layer **111**.

In a case where the conductive support substrate **110** is arranged, the conductive support substrate **110** is positioned in the base and the growth substrate **101** is then removed. The growth substrate **101** may be removed by a physical and/or chemical method and one example of the physical method is a laser lift off (LLO) manner.

Meanwhile, although not shown, after removal of the growth substrate **101**, the buffer layer (not shown) arranged on the light-emitting structure **150** may be removed. At this time, the buffer layer (not shown) may be removed by a dry- or wet-etching method, or a polishing process.

Referring to FIGS. 7 and 8, the peripheral regions of the light-emitting structure **150** are mesa-etched and an insulating layer **170** is then arranged. By mesa-etching the light-emitting structure **150**, the width of the active layer **152** may be larger than that of the reflective layer **120** and an area of the reflective layer **120** is larger than that of the active layer **152**, thus further improving reflectivity of the reflective layer **120**.

The insulating layer **170** may be made of an insulating material and may extend from the top of the protective layer **140**, which does not vertically overlap the light-emitting structure **150** along the side of the light-emitting structure **150** to the partial top of the first semiconductor layer **151**.

Referring to FIG. 9, the surface of the first conductive semiconductor layer **151** is partially or entirely etched by a predetermined etching method to form a light extraction structure **158** and a second electrode layer **160** on the first conductive semiconductor layer **151**.

The light extraction structure **158** may be not formed in some cases and the structure thereof is not limited to that illustrated in FIG. 9.

Meanwhile, the second electrode layer **160** vertically overlaps the current blocking layer **180** in at least one region. That is, the current blocking layer **180** is arranged such that it corresponds to the position of the second electrode layer **160**, thus preventing electron crowding in which electrons supplied through the second electrode layer **160** are concentrated on only the bottom of the second electrode layer **160**.

FIG. 10A is a perspective view illustrating a light-emitting device package according to one embodiment. FIG. 11B is a sectional view of the light-emitting device package illustrated in FIG. 10A.

Referring to FIGS. 10A and 10B, the light-emitting device package **200** according to the embodiment includes a body **210** having a cavity **220**, first and second lead frames **240** and **250** mounted in the body **210**, and a light-emitting device **230** electrically connected to the first and second lead frames **240** and **250**.

The body **21** may be made of at least one selected from resins such as polyphthalamide (PPA), silicon (Si), aluminum (Al), aluminum nitride (AlN), aluminum oxide (AlOx), photosensitive glass (PSG), polyamide 9T (PA9T), syndiotactic polystyrene (SPS), a metal, sapphire (Al₂O₃), beryllium oxide (BeO), ceramic, a printed circuit board (PCB) and ceramic. The body **210** may be formed by injection molding, etching and the like and the present embodiments is not limited to this formation method.

The inner surface of the body **210** may be provided with an inclined surface. The reflective angle of light emitted from the light-emitting device **230** may be varied, depending on the angle of the inclined surface. Accordingly, the orientation angle of light discharged to the outside can be controlled.

Meanwhile, as seen from the top, the cavity provided in the body **210** may have various shapes including, without being limited to, a circular shape, a rectangular shape, a polygonal shape, an oval shape and a shape with curved corners.

A resin layer may be formed in the cavity and the resin layer may include a phosphor (not shown). The resin layer may be made of transparent silicone, epoxy and other resins and may be formed by filling the cavity with a resin, followed by curing using UV or heat.

The phosphor (not shown) is selected, taking into consideration the wavelength of light emitted from the light-emitting device **230** to allow the light-emitting device package **200** to render white light.

The phosphor included in the resin layer may be at least one of blue light-emitting phosphors, blue-green light-emitting phosphors, green light-emitting phosphors, yellow-green light-emitting phosphors, yellow light-emitting phosphors, yellow-red light-emitting phosphors, orange light-emitting phosphors, and red light-emitting phosphors.

That is, the phosphor (now shown) is excited by first light emitted from the light-emitting device **230** to produce second light. For example, in a case where the light-emitting device **230** is a blue light-emitting diode and the phosphor (not shown) is a yellow phosphor, the yellow phosphor is excited by blue light to emit yellow light, blue light emitted from the blue light-emitting diode is mixed with yellow light excited and generated by blue light to allow the light-emitting device package **200** to render white light.

Similarly, in the case where the light-emitting device **230** is a green light-emitting diode, a magenta phosphor or a combination of blue and red phosphors may be exemplified, and in the case where the light-emitting device **230** is a red light-emitting diode, a cyan phosphor or a combination of blue and green phosphors may be exemplified.

Such a phosphor may be a known phosphor such as YAG, TAG, sulfides, silicates, aluminates, nitrides, carbides, nitridosilicates, borates, fluorides and phosphates.

Meanwhile, the body **210** may be provided with the first lead frame **240** and the second lead frame **250**. The first lead frame **240** and the second lead frame **250** are electrically connected to the light-emitting device **230** to supply electricity to the light-emitting device **230**.

The first lead frame **240** and the second lead frame **250** are electrically separated from each other, to reflect light emitted from the light-emitting device **230** and thereby improve light efficiency and discharge heat emitted from the light-emitting device **230** to the outside.

FIGS. 10A and 10B illustrate a case in which the light-emitting device **230** is provided on the first lead frame **250**, although the present embodiments is not limited to this configuration. The light-emitting device **230** may be electrically connected to the first lead frame **240** and second lead frame **250** by wire bonding, flip chip or die bonding.

The first lead frame **240** and second lead frame **250** may contain a metal such as titanium (Ti), copper (Cu), nickel (Ni), gold (Au), chrome (Cr), tantalum (Ta), platinum (Pt), tin (Sn), silver (Ag), phosphorus (P), aluminum (Al), indium (In), palladium (Pd), cobalt (Co), silicon (Si), germanium (Ge), hafnium (Hf), ruthenium (Ru), iron (Fe), and an alloy thereof. In addition, the first and second lead frames **240** and **250** may have a monolayer or multilayer structure, without being limited thereto.

FIG. 11A is a perspective view illustrating a lighting device including a light-emitting device according to one embodiment. FIG. 11B is a sectional view of the lighting device taken along the line A-A of FIG. 1.

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Meanwhile, hereinafter, for better understanding, the lighting device **300** will be described based on a longitudinal direction Z, a horizontal direction Y vertical to the longitudinal direction Z, and a height direction X vertical to the longitudinal direction Z and the horizontal direction Y.

That is, FIG. **11B** is a sectional view of the lighting device **300** of FIG. **11A**, taken along the cross-section of the longitudinal direction (Z) and height direction (X) and seen from the horizontal direction (Y).

Referring to FIGS. **11A** and **11B**, the lighting device **300** may include a body **310**, a cover **330** connected to the body **310** and an end cap **350** arranged at both ends of the body **310**.

A light-emitting device module **340** is connected to the bottom of the body **310** and the body **310** may be composed of a metal which exhibits superior conductivity and excellent heat release effects in order to discharge heat generated from the light-emitting device package **344** to the outside through the top of the body **310**.

The light-emitting device module includes a PCB **342** and a light-emitting device package **344** including a light-emitting device (not shown). The light-emitting device package **344** is mounted on the PCB **342** in multiple colors and multiple rows to constitute an array, and may be spaced from one another by a predetermined distance or by different distances, as necessary, to control brightness. The PCB **342** may be a metal core PCB (MCPCB) or a PCB made of FR4.

The cover **330** may take the shape of a circle to surround the bottom of the body **310**, without being limited thereto.

The cover **330** protects the light-emitting device module **340** from foreign substances. In addition, the cover **330** prevents glare generated from the light-emitting device package **344** and includes diffusion particles to uniformly discharge light to the outside. In addition, a prism pattern or the like may be formed on at least one of the inner and outer surfaces of the cover **330**. Alternatively, a phosphor may be applied onto at least one of the inner and outer surfaces of the cover **330**.

Meanwhile, the cover **330** should exhibit superior light transmittance, so that it can discharge light generated from the light-emitting device package **344** through the cover **330** to the outside, and the cover **330** should exhibit sufficient heat resistance so that it can endure heat emitted by the light-emitting device package **344**. Preferably, the cover **330** is composed of a material including polyethylene terephthalate (PET), polycarbonate (PC) or polymethyl methacrylate (PMMA) and the like.

The end cap **350** is arranged on both ends of the body **310** and may be used to seal a power device (not shown). In addition, the end cap **350** is provided with a power pin **352**, allowing the lighting device **300** to be applied to a conventional terminal from which a fluorescent light has been removed, without using any additional device.

FIG. **12** is an exploded perspective view illustrating a liquid crystal display including the light-emitting device according to another embodiment.

FIG. **12** illustrates an edge-light type liquid crystal display device **400** which includes a liquid crystal display panel **410** and a backlight unit **470** to supply light to the liquid crystal display panel **410**.

The liquid crystal display panel **410** displays an image using light supplied from the backlight unit **470**. The liquid crystal display panel **410** includes a color filter substrate **412** and a thin film transistor substrate **414** which face each other such that liquid crystal is interposed therebetween.

The color filter substrate **412** can realize color images to be displayed through the liquid crystal display panel **410**.

The thin film transistor substrate **414** is electrically connected to a printed circuit board **718** on which a plurality of

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circuit components is mounted through a driving film **417**. The thin film transistor substrate **414** responds to drive signals supplied from the printed circuit board **418** and may apply drive voltage from the printed circuit board **418** to liquid crystals.

The thin film transistor substrate **414** includes a thin film transistor and a pixel electrode formed as a thin film on other substrates composed of a transparent material such as glass or plastic.

The backlight unit **470** includes a light-emitting device module **420** to emit light, a light guide plate **430** to convert light emitted from the light-emitting device module **420** into a surface light source and supply the light to the liquid crystal display panel **410**, a plurality of films **450**, **466** and **464** to uniformize brightness of light from the light guide plate **430** and improve vertical incidence, and a reflective sheet **440** to reflect light emitted to the back of the light guide plate **430** to the light guide plate **430**.

The light-emitting device module **420** includes a plurality of light-emitting device packages **424** and a PCB **422** on which the light-emitting device packages **424** are mounted to form an array.

In particular, the light-emitting device included in the light-emitting device package **424** is the same as mentioned with reference to FIG. **1**.

Meanwhile, the backlight unit **470** includes a diffusion film **466** to diffuse light incident from the light guide plate **430** toward the liquid crystal display panel **410**, a prism film **450** to concentrate the diffused light and thus improve vertical incidence and a protective film **464** to protect the prism film **450**.

FIG. **13** is an exploded perspective view illustrating a liquid crystal display including the light-emitting device according to one embodiment.

The contents illustrated and described in FIG. **12** are not mentioned in detail.

FIG. **13** illustrates a direct-type liquid crystal display device **500** which includes a liquid crystal display panel **510** and a backlight unit **570** to supply light to the liquid crystal display panel **510**.

The liquid crystal display panel **510** has been described in FIG. **13** and a detailed explanation thereof is thus omitted.

The backlight unit **570** includes a plurality of light-emitting device modules **523**, a reflective sheet **524**, a lower chassis **530** in which the light-emitting device modules **523** and the reflective sheet **524** are accepted, and a diffusion plate **540** and a plurality of optical films **560** arranged on the light-emitting device modules **523**.

Each light-emitting device module **523** includes a plurality of light-emitting device packages and a PCB **521** on which the light-emitting device packages **524** are mounted to form an array.

The reflective sheet **524** reflects light generated by the light-emitting device package **822** toward the liquid crystal display panel **510** to improve luminous efficacy.

Meanwhile, light emitted from the light-emitting device module **523** is incident on the diffusion plate **540** and an optical film **560** is arranged on the diffusion plate **540**. The optical film **560** includes a diffusion film **566**, a prism film **550** and a protective film **564**.

In the embodiments, the lighting device and the backlight unit may be included in the lighting system and the present embodiments are not limited thereto.

The features, structures and effects illustrated in the above embodiments may be included in at least one embodiment, but are not limited to one embodiment. Further, those skilled in the art will appreciate that various combinations and modi-

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fications of the features, structures and effects illustrated in the respective embodiments are possible. Therefore, it will be understood that these combinations and modifications are within the scope of the embodiments.

Although the embodiments have been disclosed for illustrative purposes, those skilled in the art will appreciate that various modifications, additions and substitutions are possible, without departing from the scope and spirit of the embodiments as disclosed in the accompanying claims. For example, the respective elements described in detail in the embodiments may be modified. Further, it will be understood that differences relating to these modifications, additions and substitutions are covered by the scope of the embodiments defined in the accompanying claims.

What is claimed is:

1. A light-emitting device comprising:

a conductive support substrate;

a reflective layer on the conductive support substrate;

a first electrode layer on the reflective layer and provided with a first step in at least one region of an edge of the first electrode layer;

a protective layer on the first step, wherein the protective layer includes at least a first layer and a second layer arranged on the first layer, wherein the first layer contains silicon dioxide (SiO_2) and the second layer contains aluminum oxide (Al_2O_3);

a light-emitting structure on the first electrode layer and the protective layer, the light-emitting structure including a first conductive semiconductor layer, a second conductive semiconductor layer and an active layer interposed between the first conductive semiconductor layer and the second conductive semiconductor layer; and

an insulating layer arranged at a side of the light-emitting structure,

wherein at least one first region of the reflective layer vertically overlaps the second layer of the protective layer, and the first step of the first electrode layer vertically overlaps the second layer of the protective layer such that the first step of the first electrode layer is between the at least one first region of the reflective layer and the second layer of the protective layer, wherein a width of the second layer of the protective layer is greater than a width of the first step,

the conductive support substrate has a wider area than the first electrode layer, and

a lower side of the light-emitting structure is disposed on an upper side of the protective layer,

wherein the insulating layer extends from a top of the protective layer along the side of the light-emitting structure to a partial top of the first semiconductor layer, and

wherein the insulating layer contacts an upper side of the protective layer.

2. The light-emitting device according to claim 1, wherein the reflective layer and the first electrode layer have the same width.

3. The light-emitting device according to claim 2, wherein a width of the region where the reflective layer and the first

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step of the first electrode layer vertically overlap the second layer of the protective layer is 15 to 30 μm .

4. The light-emitting device according to claim 3, wherein a width of the region where the reflective layer and the first step of the first electrode layer overlap the second layer of the protective layer is 0.11- to 0.23-fold of the width of the protective layer.

5. The light-emitting device according to claim 4, further comprising:

a light extraction structure on the light-emitting structure.

6. The light-emitting device according to claim 5, wherein the light extraction structure comprises a roughness having a predetermined roughness level.

7. The light-emitting device according to claim 1, further comprising:

a second electrode layer on the light-emitting structure.

8. The light-emitting device according to claim 7, further comprising a current blocking layer under the light-emitting structure such that the current blocking layer vertically overlaps the second electrode layer in at least one region.

9. The light-emitting device according to claim 8, wherein the first electrode layer comprises a step in a region where the first electrode layer vertically overlaps the second electrode layer,

wherein the current blocking layer is in the step.

10. The light-emitting device according to claim 1, wherein the reflective layer contains at least one of Ag, Ni, Al, Rh, Pd, Ir, Ru, Mg, Zn, Pt, Au, Hf, IZO, IZTO, IAZO, IGZO, IGTO, AZO and ATO.

11. The light-emitting device according to claim 1, wherein the area of the reflective layer is larger than the area of the active layer.

12. A lighting system comprising the light-emitting device according to claim 1.

13. The light-emitting device according to claim 1, wherein the insulating layer disposed on top of the first semiconductor layer overlaps the protective layer.

14. The light-emitting device according to claim 9, wherein the current blocking layer includes a first layer and a second layer on the first layer such that the second layer is between the first layer of the current blocking layer and the first electrode layer.

15. The light-emitting device according to claim 1, wherein the first electrode layer is provided with a second step in at least one region on another edge of the first electrode layer, and the first electrode layer is a continuous layer from the first step to the second step.

16. The light-emitting device according to claim 15, wherein at least one second region of the reflective layer vertically overlaps the second layer of the protective layer, and the second step of the first electrode layer vertically overlaps the second layer of the protective layer such that the second step of the first electrode layer is between the at least one second region of the reflective layer and the second layer of the protective layer, and the reflective layer is a continuous layer from the at least one first region to the at least one second region.

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